

L Number	Hits	Search Text	DB	Time stamp
-	124	250/49\$.ccls. and shaping adj aperture	USPAT; EPO; JPO; DERWENT	2002/11/05 11:06
-	19	(250/49\$.ccls. and shaping adj aperture) and raster	USPAT; EPO; JPO; DERWENT	2002/11/05 08:03
-	9	250/49\$.ccls. and shaping adj aperture and mesh	USPAT; EPO; JPO; DERWENT	2002/11/05 09:11
-	4	250/49\$.ccls. and shadow adj pattern	USPAT; EPO; JPO; DERWENT	2002/11/05 09:14
-	102	(250/49\$.ccls. and shaping adj aperture) and deflector	USPAT; EPO; JPO; DERWENT	2002/11/05 11:06
-	4609	250/492\$.ccls. and beam	USPAT; EPO; JPO; DERWENT	2002/11/05 11:15
-	934	(250/492\$.ccls. and beam) and lithography	USPAT; EPO; JPO; DERWENT	2002/11/05 12:32
-	393	(250/492\$.ccls. and beam) and lithography and particle	USPAT	2002/11/05 11:17
-	245	(250/492\$.ccls. and beam) and lithography and particle and aperture	USPAT	2002/11/05 16:02
-	52	(250/492\$.ccls. and beam) and lithography and particle and aperture and offset	USPAT	2002/11/05 14:24
-	46	(250/492\$.ccls. and beam) and lithography and mesh	USPAT; EPO; JPO; DERWENT	2002/11/05 16:39
-	1	((250/492\$.ccls. and beam) and lithography and mesh) and array with target	USPAT; EPO; JPO; DERWENT	2002/11/05 12:54
-	44	(250/492\$.ccls. and beam) and lithography and particle and aperture and angl\$6 and offset	USPAT	2002/11/05 15:50
-	12	spot adj exposure adj time	USPAT	2002/11/05 15:50
-	16	(250/492\$.ccls. and beam) and lithography and particle and aperture and fiducial	USPAT	2002/11/05 16:02